The Seventh International Surface Cleaning Workshop Agenda

Northeastern University Campus: Raytheon Amphitheater

October 28th-29th, 2010

Thursday, October 28th, 2010	
8:30-9:00	**Registration & Breakfast - Raytheon Amphitheater**
9:00 - 9:10	**Welcome - Ahmed Busnaina**
	Session 1, Session Chair: Jingoo Park
9:10 - 9:40	Jae Hyuck Choi - Samsung
	Current Status and Challenges of EUV Mask Cleaning from Industrial Perspectives
9:40-10:10	Mark Thirsk - Linx Consulting
	Emerging Materials in Advanced Devices
10:10-10:40	Takeshi Hattori - Hattori Consulting International
	Ultra Pure Water-Related Problems and their Solutions in Advanced Semicondctor Manufacturing
10:40-11:00	**Break**
	Session 2, Session Chair: Rick Reidy
11:00-11:30	Andreas Klipp - BASF
	Development of Advanced Post Copper CMP Clean Solutions for Future Technology Nodes
11:30-12:00	Rakesh Singh - Entegris Inc
	Post-CMP Cleaning Challenges and Opportunities
12:00-12:30	Shohei Shima - Ebara Corporation
	Measurements of Surface Potential Non-uniformities Using KFM and EFM Techniques for Analyzing Localized Defects During CMP Process
12:30-2:00	**LUNCH**
	Session 3, Session Chair: Joel Barnett
2:00-2:30	Chung-Kyung Jung - Dongbu HiTek
	A Study of Environmental Cleaning Process for Advanced Copper / low-k Device without the use of DMAC (dimethylacetamide)
2:30-3:00	Kevin McLaughlin - ATMI
	Surface Preparation Beyond 32nm: Development of Engineered Chemistries for HKMG and Cu/ULK Applications
3:00-3:30	Tae-Gon Kim - IMEC
	Insight of Chemical Mechanical Cleaning and Its Future
3:30-4:00	**Break**
	Session 4, Session Chair: CK Jung
4:00-4:30	Ismail Kashkoush - Akrion Systems
	Wet Surface Conditioning of Monocrystalline Silicon Prior to Alkaline Texturization
4:30-5:00	Jin-Goo Park - Hanyang University
	The Characterization and Application of Gas Dissolved DI Water to Next Generation Semiconductor Wet Process
5:00-7:30	**Reception (406 Egan Research Center)**

Friday, October 29th, 2010

8:30-9:10	**Registration & Breakfast - 440 Egan Research Center**
	Session 5, Session Chair: Andreas Klipp
9:10 - 9:40	Joel Barnett - Sematech
	III-V materials Cleaning challenges
9:40-10:10	Michael Fury - Techcet Group
	Surface Cleaning Supply Chains: Where Will the Future Come From?
10:10-10:40	Ahmed Busnaina - Northeastern Univsersity
	Fundamentals of Surface Cleaning
10:40-11:00	**Break**
	Session 6, Session Chair: Hattori
11:00-11:30	Richard Reidy - University of North Texas
	The Effects of Plasma and Chemical Modification on Wetting of Low-k Films
11:30-12:00	Mark Litchy - CT Associates
	Effect of Pump Pulsation and Particle Loading on Membrane Filter Particle Performance
12:00-12:30	JS Choi, IMT
	Cryogenic Aerosol Cleaning
12:30-1:30	**LUNCH**
	Session 7, Session Chair: JS Choi
1:30-2:00	Dongsik Kim - Postech University
	Novel Surface Cleaning Process by Laser-induced Micro Liquid Jet
2:00-2:30	Taehoon Kim - Northeastern University
	Study on Removal Mechanism of Nanoscale Particles in Wet Laser Shockwave Cleaning
2:30-3:00	**Break**
	Session 8, Session Chair: DS Kim
3:00-3:30	Duck Joo Moon - MCK
	FPD Glass Surface Preparation; Its Overview and Challenges
3:30-4:00	Jacob Andrews and Tetsu Kohyama - Entegris Inc
	Advancements in Liquid Purification Technologies Using High-purity Polymer-based Membrane Filters